

## GRC Patterning Review Agenda

Date: Wednesday, August 24, 2011 – Thursday, August 25, 2011

Location: 540 A/B Cory Hall, UC-Berkeley Campus, Berkeley, CA

<b>Wednesday, August 24, 2011</b>		
8:00 - 9:00 a.m.	Registration	
	Continental Breakfast	
8:30 - 9:00 a.m.	Patterning TAB Caucus (Closed Meeting - Industry Members Only)	
9:00 - 9:05 a.m.	Introductory Remarks	Daniel Herr SRC
9:05 - 9:15 a.m.	Welcome and Announcements	Jeffrey Bokor UC-Berkeley
9:15 - 10:15 a.m.	1388.001 - SRC Association with Center for Hierarchical Manufacturing	James Watkins, U. of Massachusetts
	1582.001 - Research on the Influence of Polymer Morphology on Dimensional Control in Lithography	
10:15 - 10:30 a.m.	Break	
10:30 – 11:00 a.m.	2131.001 - Design Rules for Directed Block Copolymer Self-Assembly	H.-S. Philip Wong Stanford
11:00 - 12:00 p.m.	1675.001 - Photoresist Design for Improved LER: Molecular Glasses as Photoresist Systems Investigated and Optimized by Combinatorial Approaches	Hans-Werner Schmidt Univ. of Bayreuth
	1675.002 - Photoresist Design for Improved LER: Resolution and Development Processes - Control of Dissolution through Macromolecular Architecture and Control of Ionic Interaction	
12:00 - 12:15 p.m.	Question & Answer Session	
12:15 - 2:00 p.m.	Lunch	
	Poster Session	
2:00 - 3:00 p.m.	Member Intra-Company Caucus (Closed Meeting - Industry Members Only)	
3:00 - 5:30 p.m.	Intercompany TAB Caucus (Closed Meeting - Industry Only)	
5:30 p.m.	Dinner	
<b>Thursday, August 25, 2011</b>		
8:00 - 9:00 a.m.	Registration	
	Continental Breakfast	
9:00 – 9:30 a.m.	1673.002 - Nano-Inkjet Printing of Active Electronic Materials	Jeffrey Bokor UC-Berkeley
	1780.001 - Technologies for Large-Array Inkjet Printing	
9:30 – 10:00 a.m.	1673.001 - Printing of Electronic Components for Polymer Substrate Enhancement	Vivek Subramanian UC-Berkeley
10:00 – 10:30	2128.001 - Controlling Image Formation in Chemically-Amplified Resists	Gila Stein U. of Houston
10:30 - 10:45	Break	

a.m.		
10:45 – 11:45 a.m.	2125.001 - Sub-Millisecond Post Exposure Bake of Chemically Amplified Resists by CO(2) Laser Heat Treatment	Christopher Ober Cornell
	2137.001 - Sub-millisecond Post-exposure Bake of Chemically Amplified Resists by CO(2) Laser Heat Treatment	
11:45 – 1:45 p.m.	Lunch & Poster Session	
1:45 – 2:15 p.m.	1856.001 - Three-Dimensional and Spectroscopic Characterization of Devices at the Atomic Scale Using Aberration-Corrected Electron Tomography	David Muller Cornell
2:15 – 2:45 p.m.	2122.001 - Focused Helium Ion Beam Induced Synthesis for Repair, Metrology Sample Preparation, and Lithography	David Joy U. Tennessee/Knoxville
2:45 – 3:15 p.m.	2121.001 - High Throughput Electron and X-ray Diffraction Based Metrology of Nanocrystalline Materials	Katayun Barmak CMU
3:15 – 3:30 p.m.	Question and Answer Session	
3:30 – 3:45 p.m.	Break	
3:45 - 4:45 p.m.	Member Intra-Company Caucus (Closed Meeting - Industry Members Only)	
4:45 – 6:45 p.m.	TAB Caucus & TAB Planning Meeting (Closed Meeting - Industry Only)	
6:45 p.m.	Review End	